

A vertical, high-magnification scanning electron micrograph (SEM) showing a chain of interconnected, star-shaped or dendritic nanogaps. The structure is highly porous and appears to be composed of many small, interconnected components, creating a series of narrow gaps along its length. The image is rendered in shades of blue and white against a dark background.

Fabrication of Nanogaps and Investigation of Molecular Junctions by Electrochemical Methods

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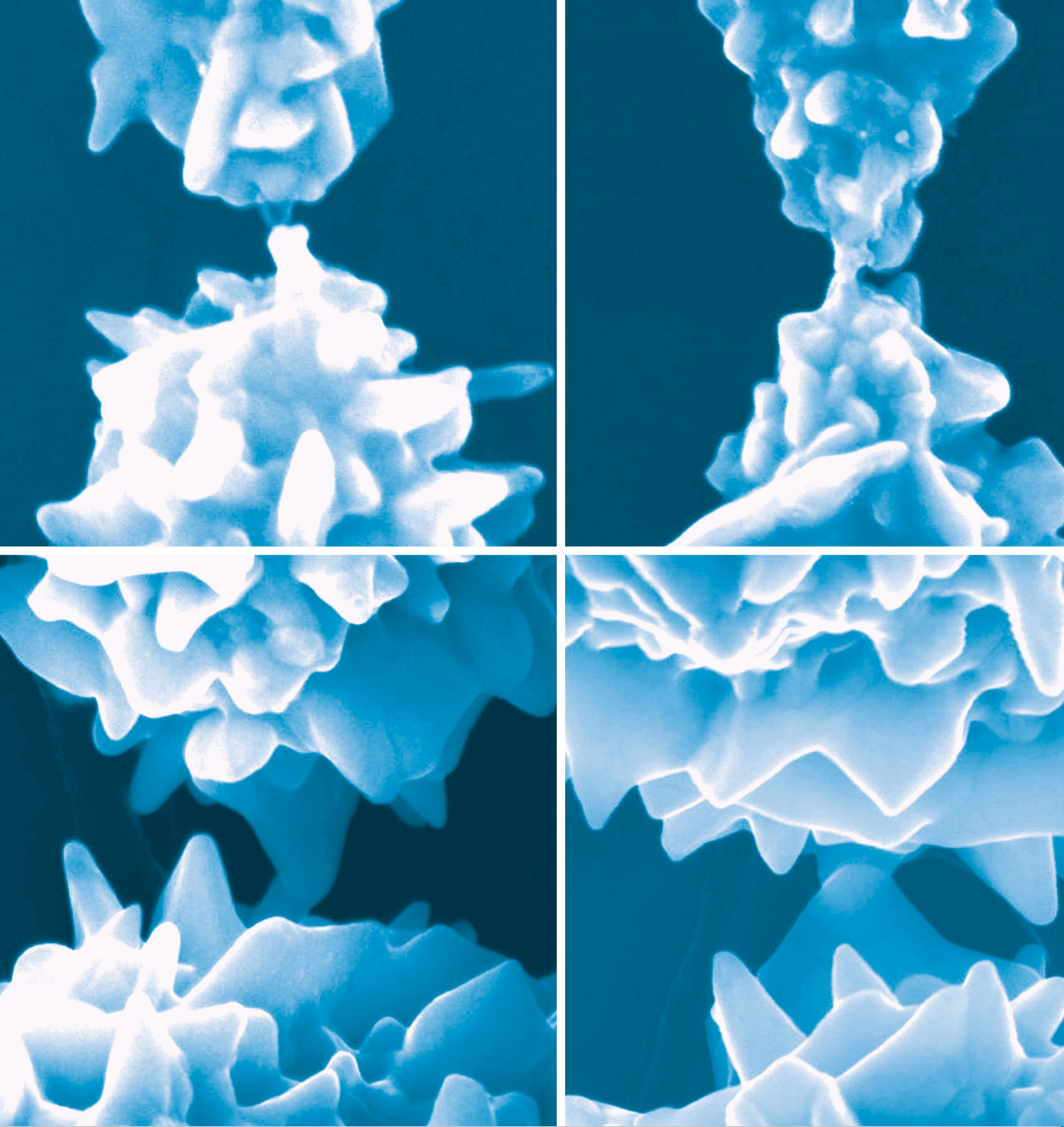
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